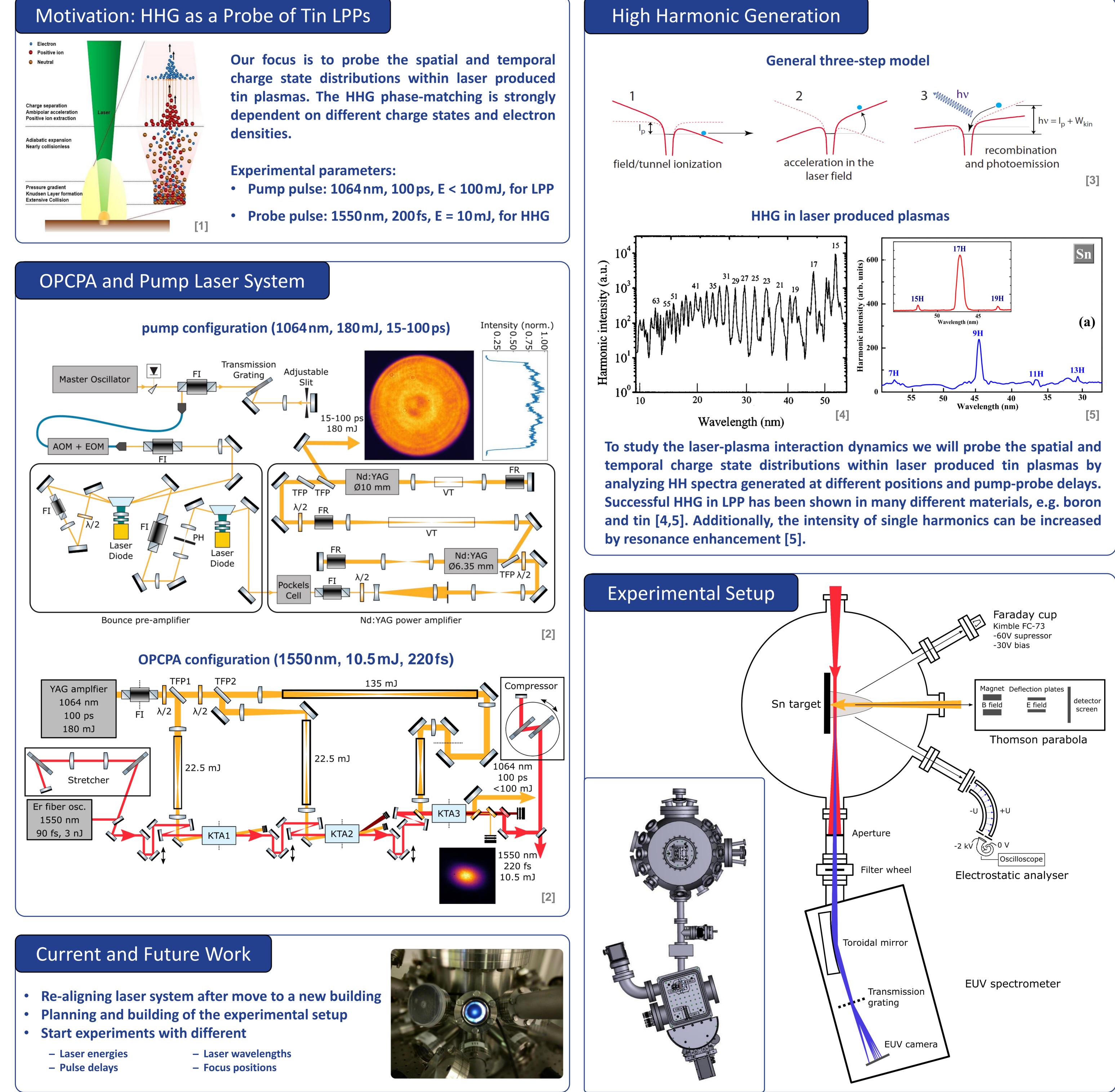
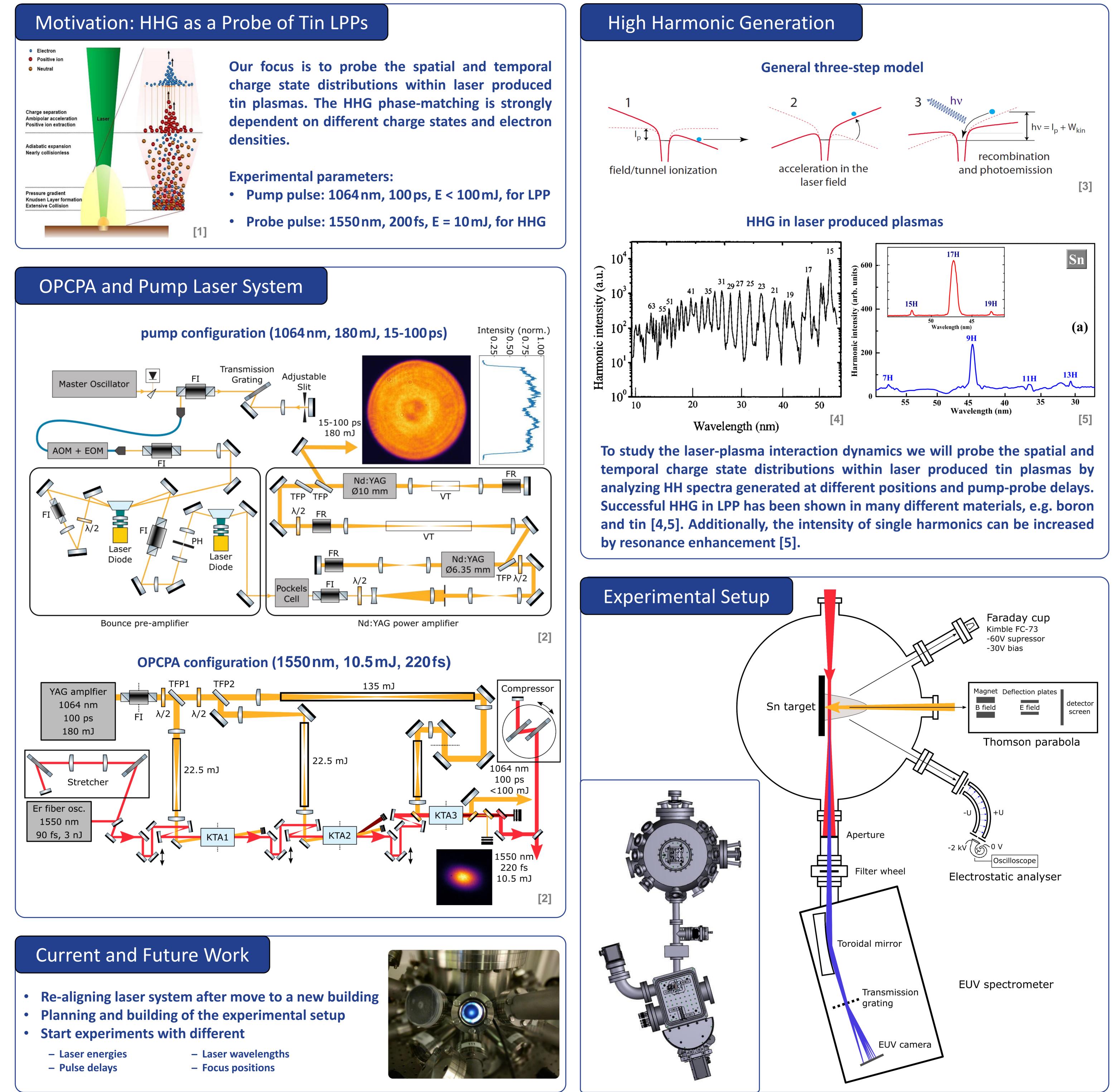


Towards High Harmonic Generation in Laser-Produced Tin Plasma

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Next-generation nanolithography devices use extreme ultraviolet (EUV) radiation, produced by a laser-produced plasma (LPP) in tin. The EUV emission Abstract characteristics of this LPP depend strongly on the plasma properties. Therefore we aim to investigate the spatial and temporal distribution of the different charge states in the tin plasma plume. For this purpose, we are developing a pump-probe experiment in which high harmonics (HH) are generated in a LPP and afterwards analysed in a spectrometer. A picosecond laser pulse will be used as a pump pulse to generate plasma. Additionally, a femtosecond pulse from a home-built optical parametric chirped pulse amplification (OPCPA) system operating at 1550 nm wavelength with tuneable pulse duration and energy will be used to generate the HH.







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